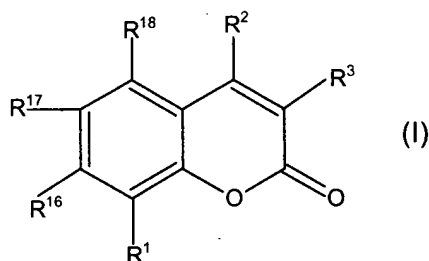


Amendments to the Claims

1 – 14. Cancelled.

15 (New). A radiation-sensitive element comprising

- (a) an aluminum substrate pretreated by electrochemical roughening and thereafter optionally anodizing or applying a hydrophilizing layer or both, wherein the electrochemical roughening is carried out with a hydrochloric acid electrolyte or an electrolyte consisting essentially of hydrochloric acid, and
- (b) a radiation-sensitive coating comprising
 - (1) at least one free-radical polymerizable monomer with at least one ethylenically unsaturated polymerizable group and at least one P-OH group,
 - (2) at least one sensitizer represented by formula (I),



wherein

- (i) R^1 , R^{16} , R^{17} and R^{18} are independently a hydrogen atom, a halogen atom, C_1 - C_{20} alkyl, -OH, -O- R^4 or -N R^5 R^6 , wherein R^4 is C_1 - C_{20} alkyl, C_5 - C_{10} aryl or C_6 - C_{30} aralkyl and R^5 and R^6 are independently a hydrogen atom or C_1 - C_{20} alkyl; or
- (ii) R^1 and R^{16} , R^{16} and R^{17} , or R^{17} and R^{18} together form a 5- or 6-membered heterocyclic ring with a N or O heteroatom in one or both positions adjacent to the phenyl ring, or

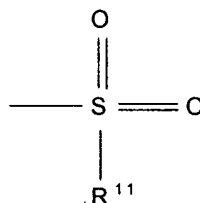
(iii) or R^1 , R^{16} and R^{17} form two adjacent 5- or 6-membered heterocyclic rings with a N or O heteroatom in a position adjacent to the phenyl ring;

wherein each formed 5- or 6-membered heterocyclic ring can independently be substituted with one or more C_1 - C_6 alkyl,

with the proviso that at least one of R^1 , R^{16} , R^{17} and R^{18} is not a hydrogen atom or C_1 - C_{20} alkyl,

R^2 is a hydrogen atom, C_1 - C_{20} alkyl, C_5 - C_{10} aryl or C_6 - C_{30} aralkyl and

R^3 is a hydrogen atom, $-\text{COOH}$, $-\text{COOR}^7$, $-\text{COR}^8$, $-\text{CONR}^9\text{R}^{10}$, $-\text{CN}$, C_5 - C_{10} aryl, C_6 - C_{30} aralkyl, a 5- or 6-membered heterocyclic ring, $-\text{CH}=\text{CH}-\text{R}^{12}$ or

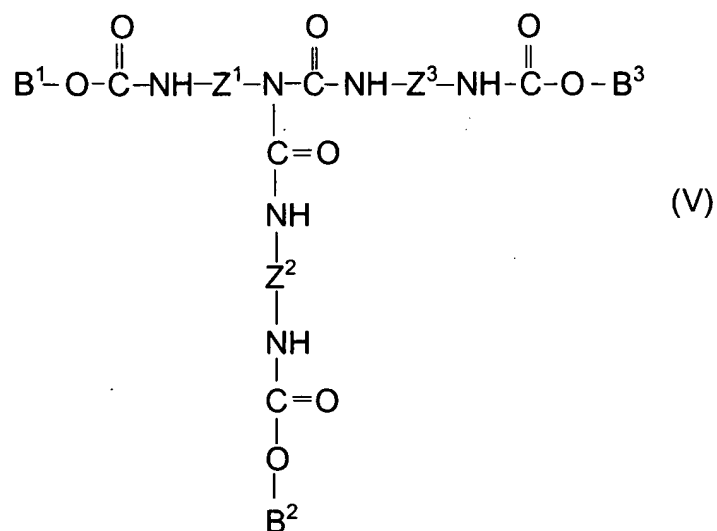


wherein R^7 is C_1 - C_{20} alkyl, R^8 is C_1 - C_{20} alkyl or a 5- or 6-membered heterocyclic ring, R^9 and R^{10} are independently a hydrogen atom or C_1 - C_{20} alkyl, R^{11} is C_1 - C_{12} alkyl or alkenyl, a heterocyclic non-aromatic ring or C_5 - C_{20} aryl optionally including an O, S or N heteroatom, and R^{12} is C_5 - C_{10} aryl or a 5- or 6-membered heterocyclic, optionally aromatic, ring;

or R^2 and R^3 , together with the carbon atoms to which they are bonded, form a 5- or 6-membered, optionally aromatic, ring;

(3) at least one onium compound, hexaarylbiimidazole compound, or trihalogenomethyl compound as a co-initiator;

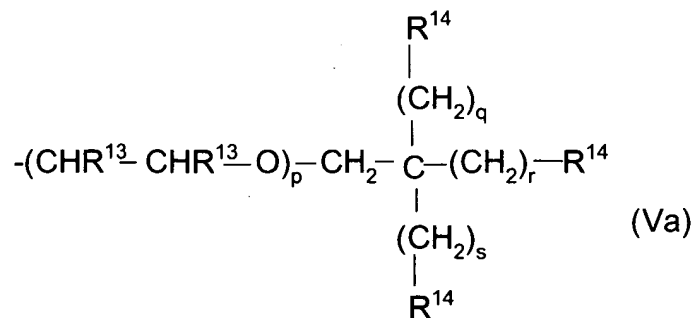
(4) at least one biuret oligomer represented by formula (V)



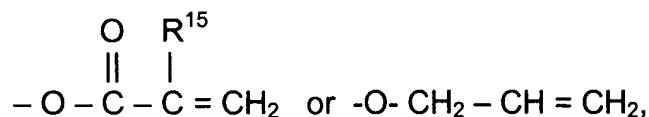
wherein Z^1 , Z^2 and Z^3 are independently $\text{C}_2\text{-C}_{18}$ alkanediyl or $\text{C}_6\text{-C}_{20}$ arylene,

B^1 , B^2 and B^3 are independently

$-(\text{CHR}^{13}-\text{CHR}^{13}-\text{O})_p-\text{CH}_2-\text{CH}=\text{CH}_2$ or a fragment represented by formula (Va)



wherein R^{13} is independently a hydrogen atom or $-\text{CH}_3$ and p is 0 or an integer from 1-10, each R^{14} is independently a hydrogen atom,



R^{15} is a hydrogen atom or C_1 - C_{12} alkyl and

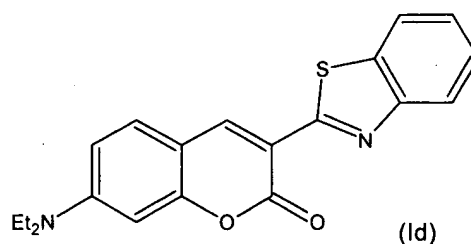
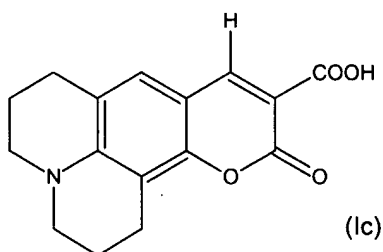
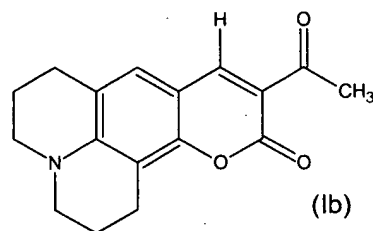
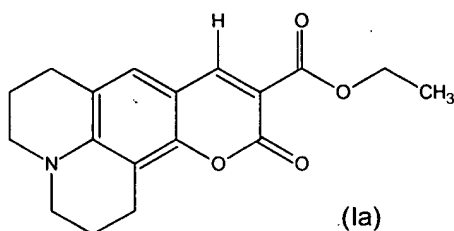
q , r and s independently of each other are 0 or 1,

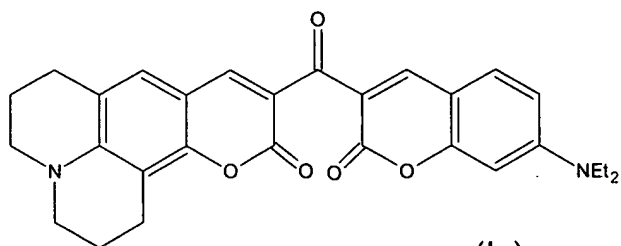
with the proviso that for B^1 , B^2 and B^3 at least one R^{14} is not a hydrogen atom if B^1 , B^2 and B^3 are all a fragment represented by formula (Va), and

(5) optionally at least one metallocene.

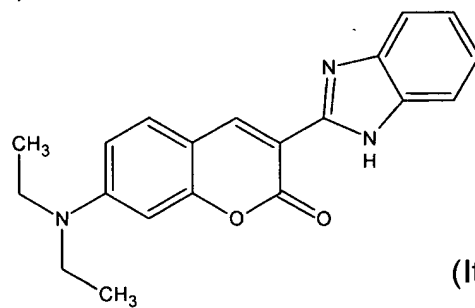
16 (New). The radiation-sensitive element according to claim 15, wherein the radiation-sensitive coating additionally comprises at least one further component comprising free-radical polymerizable monomers, oligomers, or prepolymers that are different from monomers (b)(1) of the radiation-sensitive coating, alkali-soluble binders, thermopolymerization inhibitors, dyes, plasticizers, chain transfer agents, leuco dyes, inorganic fillers or surfactants.

17 (New). The radiation-sensitive element according to claim 15, wherein the sensitizer is represented by formulas Ia-Ih, Ij-Ik and Im-Iq, or mixtures thereof:

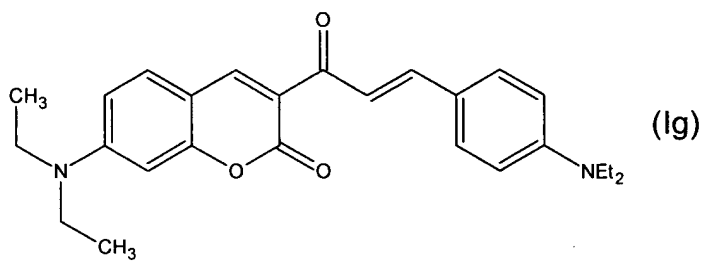




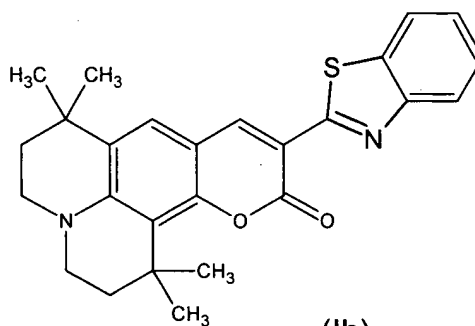
(le)



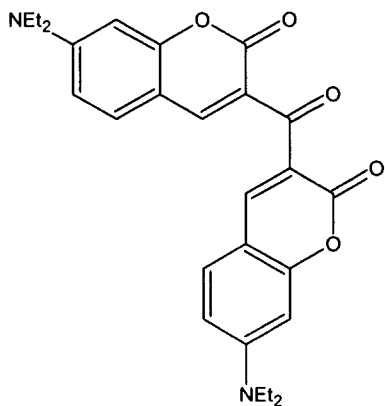
(lf)



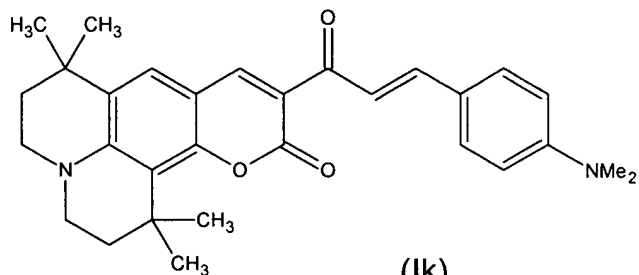
(lg)



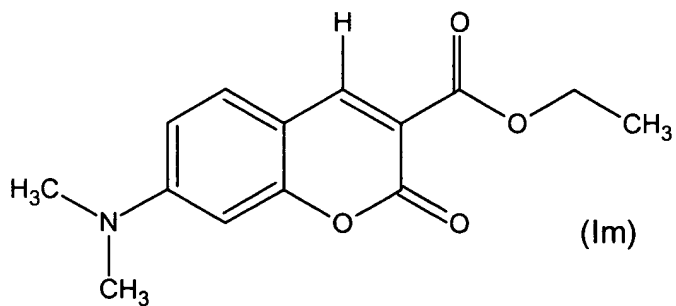
(lh)



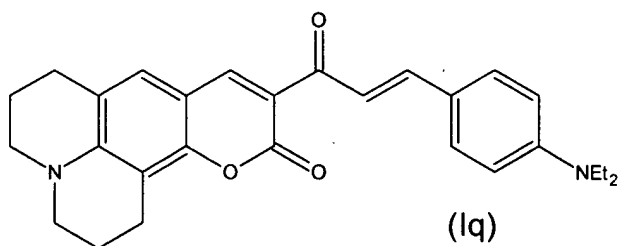
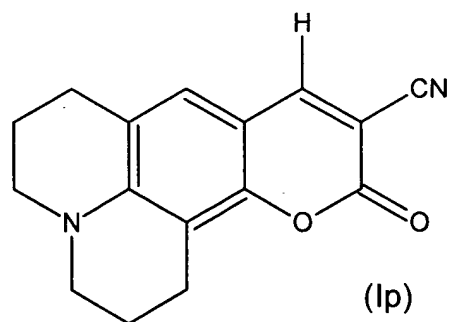
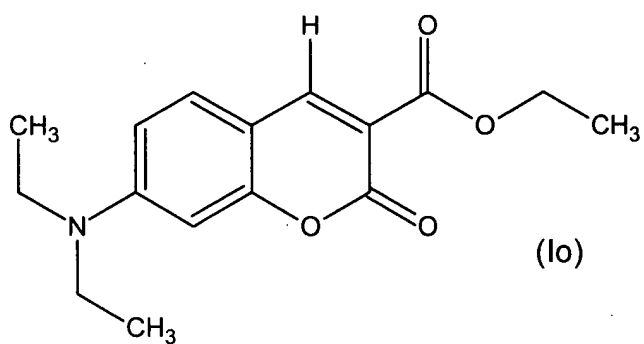
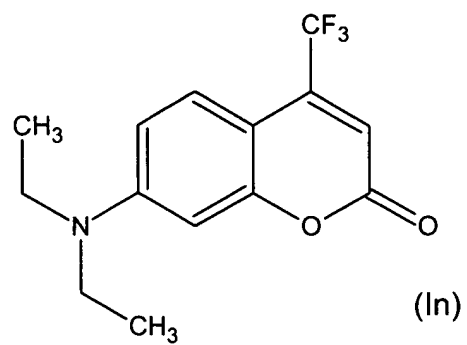
(lj)



(lk)



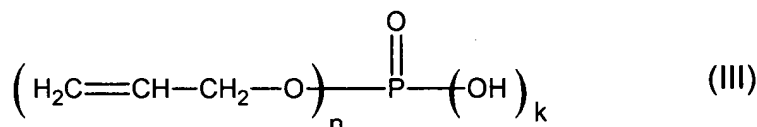
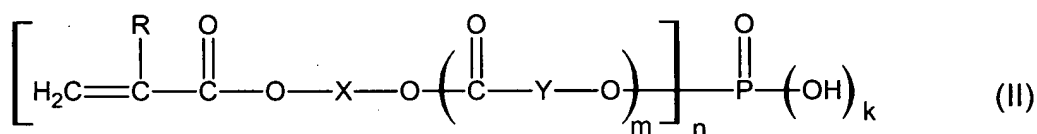
(lm)



18 (New). The radiation-sensitive element according to claim 15, wherein the coinitiator is an iodonium compound or a hexaarylbiimidazole compound.

19 (New). The radiation-sensitive element according to claim 15, wherein the radiation-sensitive coating comprises a metallocene with a metal of the fourth subgroup as a central atom.

20 (New). The radiation-sensitive element according to claim 15, wherein the free-radical polymerizable monomer with at least one ethylenically unsaturated group and at least one P-OH group is represented by formulas (II) and (III):



wherein n is 1 or 2,

m is 0 or 1,

k is 1 or 2,

n + k = 3,

R is a hydrogen atom or C₁-C₁₂ alkyl,

X is C₂-C₁₂ alkanediyl and

Y is C₂-C₁₂ alkanediyl.

21 (New). The radiation-sensitive element according to claim 15, wherein in the biuret of formula (V) each of Z¹, Z², and Z³ are the same.

22 (New). The radiation-sensitive element according to claim 15, wherein an oxygen-impermeable overcoat is provided on the radiation-sensitive coating.

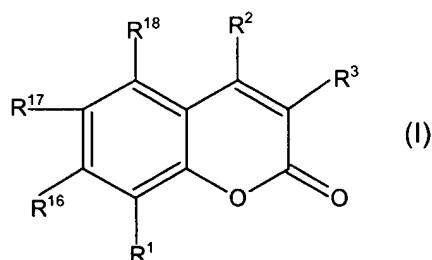
23 (New). A process for the production of an imaged element comprising the steps of:

(a) providing a radiation-sensitive element comprising

(1) an aluminum substrate pretreated by electrochemical roughening and thereafter optionally anodizing or applying a hydrophilizing layer or both, wherein the electrochemical roughening is carried out with a hydrochloric acid electrolyte or an electrolyte consisting essentially of hydrochloric acid, and

(2) a radiation-sensitive coating comprising

- (i) at least one free-radical polymerizable monomer with at least one ethylenically unsaturated polymerizable group and at least one P-OH group,
(ii) at least one sensitizer represented by formula (I),



wherein

- (a) R^1 , R^{16} , R^{17} and R^{18} are independently a hydrogen atom, a halogen atom, C_1 - C_{20} alkyl, -OH, -O- R^4 or -NR⁵R⁶, wherein R^4 is C_1 - C_{20} alkyl, C_5 - C_{10} aryl or C_6 - C_{30} aralkyl and R^5 and R^6 are independently a hydrogen atom or C_1 - C_{20} alkyl; or
- (b) R^1 and R^{16} , R^{16} and R^{17} , or R^{17} and R^{18} together form a 5- or 6-membered heterocyclic ring with a N or O heteroatom in one or both positions adjacent to the phenyl ring, or

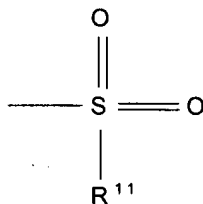
(c) or R^1 , R^{16} and R^{17} form two adjacent 5- or 6-membered heterocyclic rings with a N or O heteroatom in a position adjacent to the phenyl ring;

wherein each formed 5- or 6-membered heterocyclic ring can independently be substituted with one or more C_1 - C_6 alkyl,

with the proviso that at least one of R^1 , R^{16} , R^{17} and R^{18} is not a hydrogen atom or C_1 - C_{20} alkyl,

R^2 is a hydrogen atom, C_1 - C_{20} alkyl, C_5 - C_{10} aryl or C_6 - C_{30} aralkyl and

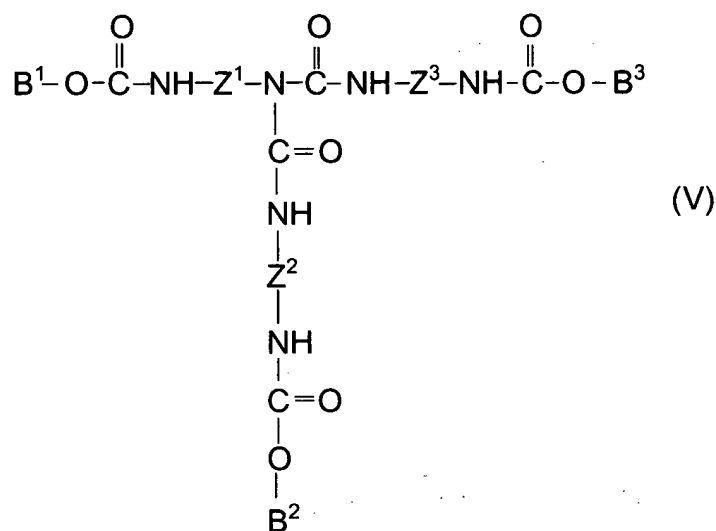
R^3 is a hydrogen atom -COOH, -COOR⁷, -COR⁸, -CONR⁹R¹⁰, -CN, C_5 - C_{10} aryl, C_6 - C_{30} aralkyl, a 5- or 6-membered heterocyclic ring, -CH=CH-R¹² or



wherein R^7 is C_1 - C_{20} alkyl, R^8 is C_1 - C_{20} alkyl or a 5- or 6-membered heterocyclic ring, R^9 and R^{10} are independently a hydrogen atom or C_1 - C_{20} alkyl, R^{11} is C_1 - C_{12} alkyl or alkenyl, a heterocyclic non-aromatic ring or C_5 - C_{20} aryl optionally including an O, S or N heteroatom, and R^{12} is C_5 - C_{10} aryl or a 5- or 6-membered heterocyclic, optionally aromatic, ring;

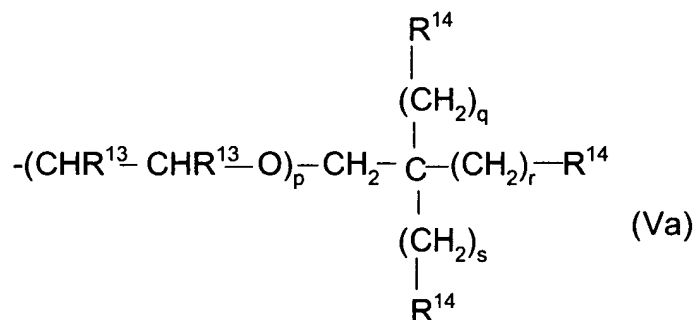
or R^2 and R^3 , together with the carbon atoms to which they are bonded, form a 5- or 6-membered, optionally aromatic, ring;

- (3) at least one onium compound, hexaarylbiimidazole compound, or trihalogenomethyl compound as a co-initiator;
- (4) at least one biuret oligomer represented by formula (V)

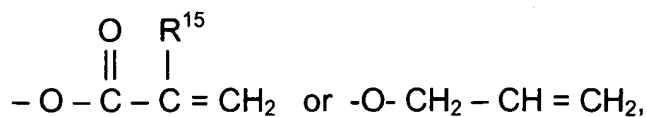


wherein Z^1 , Z^2 and Z^3 are independently $\text{C}_2\text{-C}_{18}$ alkanediyl or $\text{C}_6\text{-C}_{20}$ arylene,

B^1 , B^2 and B^3 are independently $-(\text{CHR}^{13}-\text{CHR}^{13}-\text{O})_p-\text{CH}_2-\text{CH}=\text{CH}_2$ or a fragment represented by formula (Va)



wherein R^{13} is independently a hydrogen atom or $-\text{CH}_3$ and p is 0 or an integer from 1-10, each R^{14} is independently a hydrogen atom,



R^{15} is a hydrogen atom or C_1 - C_{12} alkyl and

q, r and s independently of each other are 0 or 1,

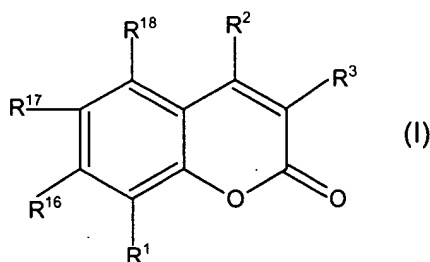
with the proviso that for B^1 , B^2 and B^3 at least one R^{14} is not a hydrogen atom if B^1 , B^2 and B^3 are all a fragment represented by formula (Va), and

(5) optionally at least one metallocene;

- (b) image-wise exposure of the element with radiation of a wavelength adjusted to the sensitizer present in the radiation-sensitive layer of the element;
- (c) optionally heating;
- (d) removing the unexposed areas with an aqueous alkaline developer; and
- (e) optionally heating the imaged element obtained in step (d) or subjecting it to overall exposure or both.

24 (New). A radiation-sensitive composition comprising

- (a) at least one free-radical polymerizable monomer with at least one ethylenically unsaturated polymerizable group and at least one P-OH group,
- (b) at least one sensitizer represented by formula (I)



wherein

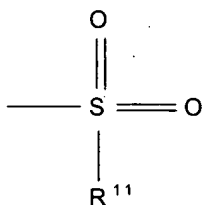
- (1) R^1 , R^{16} , R^{17} and R^{18} are independently a hydrogen atom, a halogen atom, C_1 - C_{20} alkyl, -OH, -O- R^4 or -NR⁵ R^6 , wherein R^4 is C_1 - C_{20} alkyl, C_5 - C_{10} aryl or C_6 - C_{30} aralkyl and R^5 and R^6 are independently a hydrogen atom or C_1 - C_{20} alkyl, or
- (2) R^1 and R^{16} , R^{16} and R^{17} , or R^{17} and R^{18} together form a 5- or 6-membered heterocyclic ring with a N or O heteroatom, in one or both positions adjacent to the phenyl ring, or
- (3) R^1 , R^{16} and R^{17} form two adjacent 5- or 6-membered heterocyclic rings with a N or O heteroatom, in a position adjacent to the phenyl ring,

wherein each formed 5- or 6-membered heterocyclic ring can independently be substituted with one or more C_1 - C_6 alkyl,

with the proviso that at least one of R^1 , R^{16} , R^{17} and R^{18} is not a hydrogen atom or C_1 - C_{20} alkyl;

R^2 is a hydrogen atom, C_1 - C_{20} alkyl, C_5 - C_{10} aryl or C_6 - C_{30} aralkyl and

R^3 is hydrogen atom, or -COOH, -COOR⁷, -COR⁸, -CONR⁹ R^{10} , -CN, C_5 - C_{10} aralkyl, a 5- or 6-membered heterocyclic ring, -CH=CH- R^{12} or



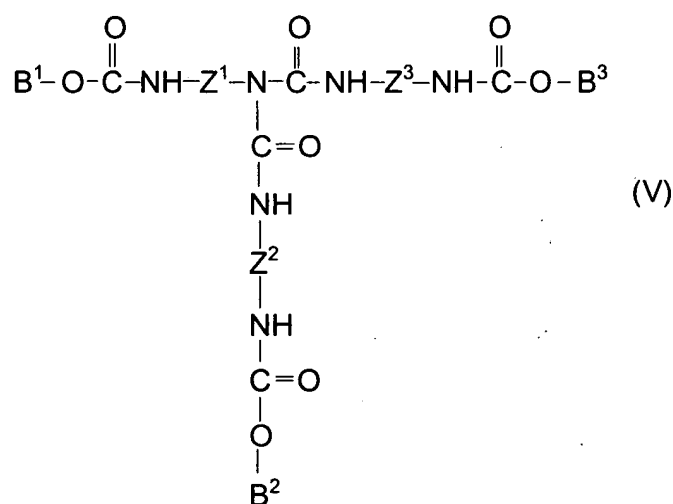
wherein R^7 is C_1 - C_{20} alkyl, R^8 is C_1 - C_{20} alkyl or a 5- or 6-membered heterocyclic ring, R^9 and R^{10} are independently a hydrogen atom or C_1 - C_{20} alkyl, R^{11} is C_1 - C_{12} alkyl, or C_1 - C_{12} alkenyl, a heterocyclic non-aromatic ring

or C₅-C₂₀ aryl optionally including an O, S or N heteroatom, and R¹² is C₅-C₁₀ aryl or a 5- or 6-membered heterocyclic, optionally aromatic, ring;

or R² and R³, together with the carbon atoms to which they are bonded, form a 5- or 6-membered, optionally aromatic, ring;

(c) at least one onium compound, hexaarylbiimidazole compound, or trihalogenomethyl compound as a coinitiator;

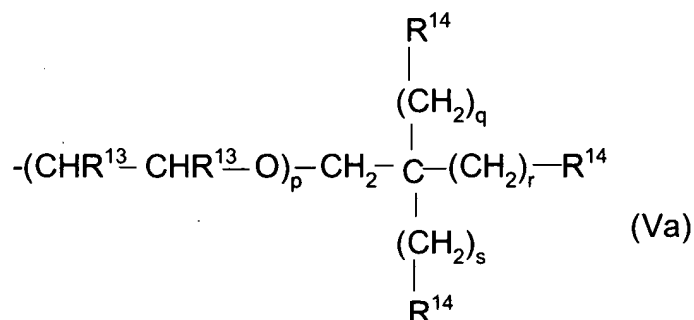
(d) at least one biuret oligomer represented by formula (V)



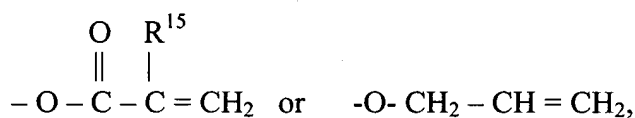
wherein Z¹, Z² and Z³ are independently C₂-C₁₈ alkanediyl or C₆-C₂₀ arylene,

B^1 , B^2 and B^3 are independently

$-(CHR^{13}-CHR^{13}-O)_p-CH_2-CH=CH_2$ or a fragment represented by formula (Va)



wherein R^{13} is independently a hydrogen atom or $-CH_3$ and p is 0 or an integer from 1-10, each R^{14} is independently a hydrogen atom,



R^{15} is a hydrogen atom or C_1 - C_{12} alkyl and

q , r and s independently of each other are 0 or 1,

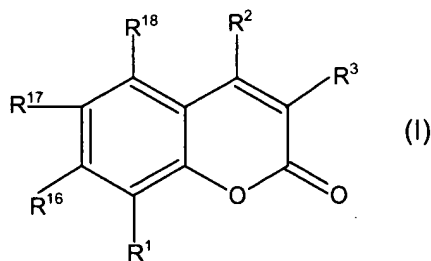
with the proviso that for B^1 , B^2 and B^3 at least one R^{14} is not a hydrogen atom if B^1 , B^2 and B^3 are all a fragment represented by formula (Va), and

- (e) a solvent or solvent mixture; and
- (f) optionally at least one metallocene.

25 (New). The radiation-sensitive composition according to claim 24, additionally comprising at least one further component comprising a free-radical polymerizable monomers, oligomers, or prepolymers that are different from monomer (a) of the radiation-sensitive composition, alkali-soluble binders, thermopolymerization inhibitors, dyes, plasticizers, chain transfer agents, leuco dyes, inorganic fillers or surfactants.

26 (New). A process for the production of a radiation-sensitive element as defined in claim 15 comprising:

- (a) providing an aluminum substrate pretreated by electrochemical roughening and thereafter optionally anodizing or applying a hydrophilizing layer or both, wherein the electrochemical roughening is carried out with a hydrochloric acid electrolyte or an electrolyte consisting essentially of hydrochloric acid;
- (b) applying a radiation-sensitive composition comprising
 - (1) at least one free-radical polymerizable monomer with at least one ethylenically unsaturated polymerizable group and at least one P-OH group,
 - (2) at least one sensitizer represented by formula (I)



wherein

- (i) R^1 , R^{16} , R^{17} and R^{18} are independently a hydrogen atom, a halogen atom, C_1 - C_{20} alkyl, -OH, -O- R^4 or -NR⁵R⁶, wherein R^4 is C_1 - C_{20} alkyl,

C₅-C₁₀ aryl or C₆-C₃₀ aralkyl and R⁵ and R⁶ are independently a hydrogen atom or C₁-C₂₀ alkyl, or

(ii) R¹ and R¹⁶, R¹⁶ and R¹⁷, or R¹⁷ and R¹⁸ together form a 5- or 6-membered heterocyclic ring with a N or O heteroatom, in one or both positions adjacent to the phenyl ring, or

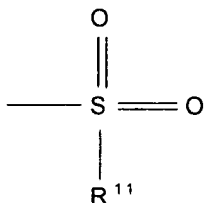
(iii) R¹, R¹⁶ and R¹⁷ form two adjacent 5- or 6-membered heterocyclic rings with a N or O heteroatom, in a position adjacent to the phenyl ring,

wherein each formed 5- or 6-membered heterocyclic ring can independently be substituted with one or more C₁-C₆ alkyl groups,

with the proviso that at least one of R¹, R¹⁶, R¹⁷ and R¹⁸ is not a hydrogen atom or C₁-C₂₀ alkyl;

R² is a hydrogen atom, C₁-C₂₀ alkyl, C₅-C₁₀ aryl or C₆-C₃₀ aralkyl and

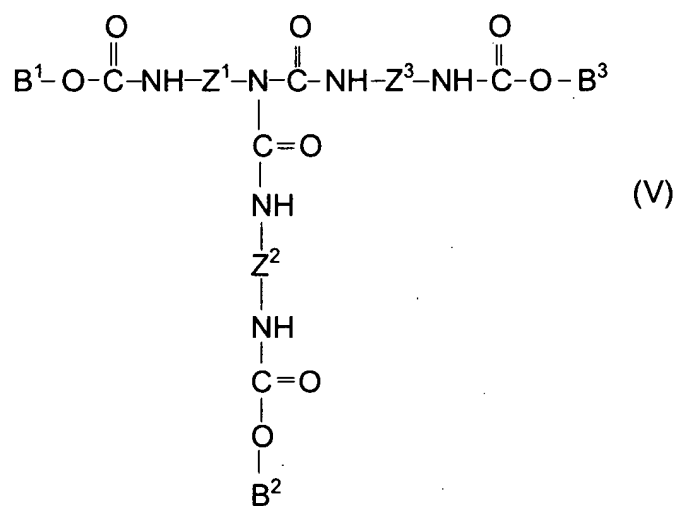
R³ is hydrogen atom, -COOH, -COOR⁷, -COR⁸, -CONR⁹R¹⁰, -CN, C₅-C₁₀ aralkyl, a 5- or 6-membered heterocyclic ring, -CH=CH-R¹² or



wherein R⁷ is C₁-C₂₀ alkyl, R⁸ is C₁-C₂₀ alkyl or a 5- or 6-membered heterocyclic ring, R⁹ and R¹⁰ are independently a hydrogen atom or C₁-C₂₀ alkyl, R¹¹ is C₁-C₁₂ alkyl, or C₁-C₁₂ alkenyl, a heterocyclic non-aromatic ring or C₅-C₂₀ aryl optionally including an O, S or N heteroatom, and R¹² is C₅-C₁₀ aryl or a 5- or 6-membered heterocyclic, optionally aromatic, ring;

or R^2 and R^3 , together with the carbon atoms to which they are bonded, form a 5- or 6-membered, optionally aromatic, ring;

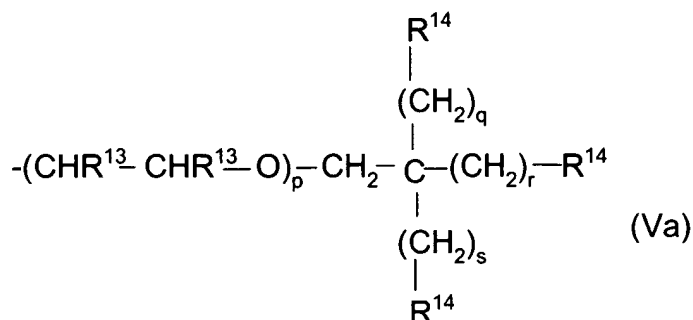
- (3) at least one onium compound, hexaarylbiimidazole compound, or trihalogenomethyl compound as a coinitiator;
- (4) at least one biuret oligomer represented by formula (V)



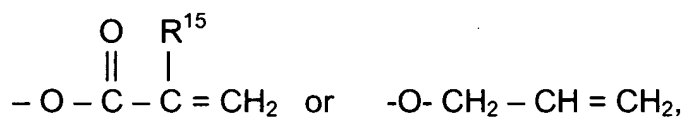
wherein Z^1 , Z^2 and Z^3 are independently $\text{C}_2\text{-C}_{18}$ alkanediyl or $\text{C}_6\text{-C}_{20}$ arylene,

B^1 , B^2 and B^3 are independently

$-(CHR^{13}-CHR^{13}-O)_p-CH_2-CH=CH_2$ or a fragment represented by formula (Va)



wherein R^{13} is independently a hydrogen atom or $-CH_3$ and p is 0 or an integer from 1-10, each R^{14} is independently a hydrogen atom,



R^{15} is a hydrogen atom or C_1-C_{12} alkyl and

q , r and s independently of each other are 0 or 1,

with the proviso that for each B^1 , B^2 and B^3 at least one R^{14} is not a hydrogen atom if B^1 , B^2 and B^3 are all a fragment represented by formula (Va), and

- (5) a solvent or solvent mixture; and
- (6) optionally at least one metallocene.

(c) drying; and

(d) optionally applying an oxygen-impermeable overcoat and drying.

27 (New). The printing form produced by the process according to claim 23.